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APPLICATION NO.	FILING DATE	FIRST NAMED INVENTOR	ATTORNEY DOCKET NO.	CONFIRMATION NO.
09/941,692	08/30/2001	Yotaro Hatamura	2001_1227	7051
7590 02/27/2004 WENDEROTH, LIND & PONACK L.L.P. Suite 800 2033 "K" Street N.W. Washington, DC 20006			EXAMINER OLSEN, ALLAN W	
			ART UNIT 1763	PAPER NUMBER

DATE MAILED: 02/27/2004

Please find below and/or attached an Office communication concerning this application or proceeding.

AS

Office Action Summary	Application No.	Applicant(s)	
	09/941,692	HATAMURA ET AL.	
	Examiner	Art Unit	
	Allan Olsen	1763	

-- The MAILING DATE of this communication appears on the cover sheet with the correspondence address --

Period for Reply

A SHORTENED STATUTORY PERIOD FOR REPLY IS SET TO EXPIRE 3 MONTH(S) FROM THE MAILING DATE OF THIS COMMUNICATION.

- Extensions of time may be available under the provisions of 37 CFR 1.136(a). In no event, however, may a reply be timely filed after SIX (6) MONTHS from the mailing date of this communication.
- If the period for reply specified above is less than thirty (30) days, a reply within the statutory minimum of thirty (30) days will be considered timely.
- If NO period for reply is specified above, the maximum statutory period will apply and will expire SIX (6) MONTHS from the mailing date of this communication.
- Failure to reply within the set or extended period for reply will, by statute, cause the application to become ABANDONED (35 U.S.C. § 133).
- Any reply received by the Office later than three months after the mailing date of this communication, even if timely filed, may reduce any earned patent term adjustment. See 37 CFR 1.704(b).

Status

- 1) ☒ Responsive to communication(s) filed on 24 December 2003.
- 2a) ☐ This action is **FINAL**. 2b) ☒ This action is non-final.
- 3) ☐ Since this application is in condition for allowance except for formal matters, prosecution as to the merits is closed in accordance with the practice under *Ex parte Quayle*, 1935 C.D. 11, 453 O.G. 213.

Disposition of Claims

- 4) ☒ Claim(s) 50-79 is/are pending in the application.
- 4a) Of the above claim(s) 78 is/are withdrawn from consideration.
- 5) ☐ Claim(s) _____ is/are allowed.
- 6) ☒ Claim(s) 50-77 and 79 is/are rejected.
- 7) ☐ Claim(s) _____ is/are objected to.
- 8) ☐ Claim(s) _____ are subject to restriction and/or election requirement.

Application Papers

- 9) ☐ The specification is objected to by the Examiner.
- 10) ☒ The drawing(s) filed on 30 August 2001 is/are: a) ☒ accepted or b) ☐ objected to by the Examiner.
Applicant may not request that any objection to the drawing(s) be held in abeyance. See 37 CFR 1.85(a).
- 11) ☐ The proposed drawing correction filed on _____ is: a) ☐ approved b) ☐ disapproved by the Examiner.
If approved, corrected drawings are required in reply to this Office action.
- 12) ☐ The oath or declaration is objected to by the Examiner.

Priority under 35 U.S.C. §§ 119 and 120

- 13) ☐ Acknowledgment is made of a claim for foreign priority under 35 U.S.C. § 119(a)-(d) or (f).
a) ☐ All b) ☐ Some * c) ☐ None of:
1. ☐ Certified copies of the priority documents have been received.
2. ☐ Certified copies of the priority documents have been received in Application No. _____.
3. ☐ Copies of the certified copies of the priority documents have been received in this National Stage application from the International Bureau (PCT Rule 17.2(a)).
* See the attached detailed Office action for a list of the certified copies not received.
- 14) ☐ Acknowledgment is made of a claim for domestic priority under 35 U.S.C. § 119(e) (to a provisional application).
a) ☐ The translation of the foreign language provisional application has been received.
- 15) ☒ Acknowledgment is made of a claim for domestic priority under 35 U.S.C. §§ 120 and/or 121.

Attachment(s)

- | | |
|--|---|
| 1) <input type="checkbox"/> Notice of References Cited (PTO-892) | 4) <input type="checkbox"/> Interview Summary (PTO-413) Paper No(s). _____ |
| 2) <input type="checkbox"/> Notice of Draftsperson's Patent Drawing Review (PTO-948) | 5) <input type="checkbox"/> Notice of Informal Patent Application (PTO-152) |
| 3) <input type="checkbox"/> Information Disclosure Statement(s) (PTO-1449) Paper No(s) _____ | 6) <input type="checkbox"/> Other: |

DETAILED ACTION

Continued Examination Under 37 CFR 1.114

A request for continued examination under 37 CFR 1.114, including the fee set forth in 37 CFR 1.17(e), was filed in this application after final rejection. Since this application is eligible for continued examination under 37 CFR 1.114, and the fee set forth in 37 CFR 1.17(e) has been timely paid, the finality of the previous Office action has been withdrawn pursuant to 37 CFR 1.114. Applicant's submission filed on 12/24/2003 has been entered.

Election/Restrictions

Newly submitted claim 78 is directed to the treatment of a thrust bearing housing which is an invention that is independent or distinct from the originally claimed methods directed to the treatment magnetic heads and related surfaces.

Since applicant has received an action on the merits for the originally presented invention, this invention has been constructively elected by original presentation for prosecution on the merits. Accordingly, claim 78 is withdrawn from consideration as being directed to a non-elected invention. See 37 CFR 1.142(b) and MPEP § 821.03.

Claim Rejections - 35 USC § 103

The following is a quotation of 35 U.S.C. 103(a) which forms the basis for all obviousness rejections set forth in this Office action:

(a) A patent may not be obtained though the invention is not identically disclosed or described as set forth in section 102 of this title, if the differences between the subject matter sought to be patented and the prior art are such that the subject matter as a whole would have been obvious at the time the invention was made to a person having ordinary skill in the art to which said subject matter pertains. Patentability shall not be negated by the manner in which the invention was made.

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This application currently names joint inventors. In considering patentability of the claims under 35 U.S.C. 103(a), the examiner presumes that the subject matter of the various claims was commonly owned at the time any inventions covered therein were made absent any evidence to the contrary. Applicant is advised of the obligation under 37 CFR 1.56 to point out the inventor and invention dates of each claim that was not commonly owned at the time a later invention was made in order for the examiner to consider the applicability of 35 U.S.C. 103(c) and potential 35 U.S.C. 102(e), (f) or (g) prior art under 35 U.S.C. 103(a).

Claims 50-63 and 68-74 are rejected under 35 U.S.C. 103(a) as being unpatentable over JP 08-257781 (hereinafter, Hatakeyama '781) in view of U.S. Patent 5,303,100 issued to Nakayama et al. (hereinafter, Nakayama).

Hatakeyama '781 teaches a method of using a fast atom beam to pattern a surface. Hatakeyama '781 teaches placing a micro dimensioned shielding mask on, or in close proximity to, the surface to be patterned. Hatakeyama '781 teaches the mask may comprise a plurality of fine wire or rods. Hatakeyama '781 teaches that the method can be used to reduce the friction between a magnetic disk and magnetic head. Hatakeyama '781 teaches that fast atom beam may impinge at an angle normal to the surface. Hatakeyama '781 teaches the contouring is very anisotropic due to highly directional nature of the particle beam. Hatakeyama '781 teaches using a mask with a plurality of square (i.e., rhombus-shaped) openings arranged in a matrix-type array. Hatakeyama '781 teaches that the fast atom beam source and the surface to be contoured can be rotated with respect to one another. Hatakeyama '781 teaches that the surface to be contoured can comprise an electrically insulating layer such as SiO₂

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or may be nickel plated. See paragraphs: 0002, 0010, 0024, 0034, 0044, 0047, 0050, 0074, 0076, 0078.

Hatakeyama '781 is directed to the method of FAB in general and while Hatakeyama teaches that the FAB bombardment method may be used to contour a slider's surface, he does not provide the specific details of such a process. For example, Hatakeyama does not teach if the substrate upon which the slider is fabricated is contoured and then a magnetic film layer and a protective film layer are formed, or if the contouring is performed on a completely fabricated slider such that the contouring beam of atoms impinges upon the protective layer of the fabricated slider. Hatakeyama does not teach the depth/height of the surface contour features. Hatakeyama does not teach a surface contour density of between 10 and 10^6 contour features /1 mm².

Nakayama teaches contouring the surface of a protective layer overlying a magnetic member. Nakayama teaches contouring the surface of a substrate upon which a magnetic film layer and a protective layer are subsequently formed. Nakayama teaches that the surface contour features should have a depth/height of the between 20 and 50 nm (column 7, line 32). Nakayama teaches contouring with a surface with 3000-6000 mesh lapping paper.

It would have been obvious to one skilled in the art to use Hatakeyama's method of contouring the surface of a magnetic slider member, by either contouring the underlying substrate before forming the magnetic film and protective film layers or by contouring the protective film of a completely fabricated slider because Nakayama teaches that both methodologies provide the desired result of reducing friction between

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two sliding members. It would have been obvious to one skilled in the art to create surface features with a depth/height of within the claimed range of between 10 and 50 nm because Nakayama teaches that this is the feature size that is effective in the reduction of friction between two sliding members. It would have been obvious to one skilled in the art to create between 10 and 10^6 surface features per 1 mm^2 of surface area because the 3000-6000 mesh lapping paper that is used by Nakayama is expected to provide contour features at a density that falls within the claimed range that spans 6 orders of magnitude.

Claims 63-67 are rejected under 35 U.S.C. 103(a) as being unpatentable over the combined teachings of Hatakeyama '781 and Nakayama, as applied to claim 50 above, and further in view of JP 08-238426 (hereinafter, Hatakeyama '426).

Hatakeyama '781 and Nakayama do not teach using a micro-particle shielding mask.

Hatakeyama '426 teaches using a micro-particle shielding mask.

It would have been obvious to one skilled in the art to use a micro-particle shielding mask because Hatakeyama '426 teaches that this enables one to achieve excellent distribution of the masking agent across the surface to be contoured.

Claims 75 and 76 are rejected under 35 U.S.C. 103(a) as being unpatentable over Hatakeyama '781 and Nakayama, as applied to claim 50 above, in view of U.S. Patent 3,947,887 issued to Platter.

Hatakeyama '781/Nakayama teaches a method of using a fast atom beam to pattern a surface. Hatakeyama '781 teaches placing a micro dimensioned shielding mask on, or in close proximity to, the surface to be patterned. Hatakeyama '781

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teaches that the method can be used to reduce the friction between a magnetic disk and magnetic head. Hatakeyama '781 teaches that fast atom beam may impinge at an angle normal to the surface. Hatakeyama '781 teaches the contouring is very anisotropic due to highly directional nature of the particle beam. See paragraphs: 0002, 0010, 0024, 0034, 0044, 0047, 0050, 0074, 0076, 0078.

Hatakeyama '781 does not teach forming micro-cavity or micro-protrusion in or on the surface of a curved slider.

Platter teaches a magnetic head with a curved surface.

It would have been obvious to one skilled in the art to apply Hatakeyama's FAB method to the magnetic head of Platter because Platters curved magnetic head because the curvature of Platter's magnetic head offers consistency of the separation between the tape and head when the tape is accelerated in a reverse direction and the micro-cavity or micro-protrusions of Hatakeyama would reduce the friction between the tape and head.

Claim 77 is rejected under 35 U.S.C. 103(a) as being unpatentable over Hatakeyama '781 and Platter, as applied to claim 75 above, and further in view of Nakayama.

Hatakeyama '781 and Platter do not teach forming a protective film layer on the micro-cavities or micro-protrusions.

Nakayama teaches forming a protective film layer over the contoured surface of a slider.

It would have been obvious to one skilled in the art to form a protective film over the contoured surface of the slider because Nakayama teaches that the standard

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practice of providing a protective film layer can be carried out after the surface of the slider has been provided with a friction reducing texture.

Claim 79 is rejected under 35 U.S.C. 103(a) as being unpatentable over Hatakeyama '781 in view of U.S. Patent 4,675,075 issued to Sakai et al. (hereinafter, Sakai).

Hatakeyama '781 teaches a method of using a fast atom beam to pattern a surface. Hatakeyama '781 teaches placing a micro dimensioned shielding mask on, or in close proximity to, the surface to be patterned. Hatakeyama '781 teaches that the method can be used to reduce the friction between a magnetic disk and magnetic head. Hatakeyama '781 teaches that fast atom beam may impinge at an angle normal to the surface. Hatakeyama '781 teaches the contouring is very anisotropic due to highly directional nature of the particle beam. See paragraphs: 0002, 0010, 0024, 0034, 0044, 0047, 0050, 0074, 0076, 0078.

Hatakeyama '781 does not teach forming two stage micro-cavity or micro-protrusion having a plurality of top stage and lower stage surfaces.

Sakai teaches a contouring a slider such that it has a multileveled surface (i.e., having a plurality of top stage and lower stage surfaces).

It would have been obvious to one skilled in the art when using Hatakeyama's FAB method to contour the surface of the slider to provide a multileveled surface because Sakai teaches that such a surface profile results in a reduction of friction and increases the resistance to wear of magnetic storage media.

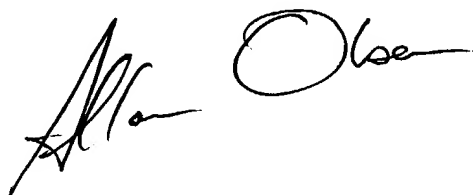
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Conclusion

Any inquiry concerning this communication or earlier communications from the examiner should be directed to Allan Olsen whose telephone number is 571-272-1441. The examiner can normally be reached on M-F 1-5.

If attempts to reach the examiner by telephone are unsuccessful, the examiner's supervisor, Greg Mills can be reached on 571-272-1439. The fax phone number for the organization where this application or proceeding is assigned is 703-872-9306.

Information regarding the status of an application may be obtained from the Patent Application Information Retrieval (PAIR) system. Status information for published applications may be obtained from either Private PAIR or Public PAIR. Status information for unpublished applications is available through Private PAIR only. For more information about the PAIR system, see <http://pair-direct.uspto.gov>. Should you have questions on access to the Private PAIR system, contact the Electronic Business Center (EBC) at 866-217-9197 (toll-free).

A handwritten signature in black ink, appearing to read "Allan Olsen". The signature is stylized, with a large "O" and a long horizontal stroke extending to the right.

Allan Olsen
Primary Examiner
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